

Appln No. 10/698,374
Amdt. Dated April 6, 2005
Response to Office Action of February 23, 2005

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Amendments to the Specification:

At Page 1, line 1 is to be deleted.

At Page 1, line 3, a new paragraph entitled "Cross Reference to Related Application" is to be added, just below the Title, as follows:

The present application is a continuation-in-part of US Application Serial No. 10/160,273 filed on June 4, 2002, now issued as US Patent No. 6,746,105, which is a continuation of US Application Serial No. 09/112,767 filed on July 10, 1998, now issued as US Patent No. 6,416,167, the entire contents of which are herein incorporated by reference.

The paragraph beginning at Page 12, lines 5-11, to be amended as follows:

The nozzle arrangement 10 includes a roof structure 72. The roof structure 72 has a roof member 74 that is positioned above the nozzle chamber wall 62. A complementary nozzle chamber wall 76 depends from the roof member 74 towards the wafer substrate 14. The complementary nozzle chamber wall 76 overlaps the outer wall portion 6466.

As can be seen in the drawings, the nozzle chamber wall ~~60-62~~ and the complementary nozzle chamber wall 76 together define a nozzle chamber 75. The nozzle chamber 75 and the ink inlet channel 22 are in fluid communication to be filled with ink 77, in use.

The paragraph beginning at Page 12, lines 20-24, through to Page 13, lines 1-2 to be amended as follows:

As can be seen in Figure 5B, when the nozzle arrangement 10 is in a quiescent condition, the meniscus 84 extends from the free edge 82 to an outer edge of the rim ~~65~~80. As can be seen in Figure 3B, when the nozzle arrangement 10 is in an initial stage of operation, the meniscus 84 extends from the free edge 82 to an inner edge of the rim 80. The re-entrant section 86 inhibits an inner edge of the meniscus 84 from moving further than the inner edge of the rim 80. Thus, wetting of a remaining portion of the outer wall portion 66 and subsequent leaking of ink is inhibited.